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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
10/679,782	10/06/2003	Marie Angelopoulos	FIS920030196US1	FIS920030196US1 3728		
23389 75	90 01/11/2006		EXAM	EXAMINER		
	OTT MURPHY & PRES	LEE, S	LEE, SIN J			
400 GARDEN (SUITE 300	CITY PLAZA	ART UNIT	PAPER NUMBER			
GARDEN CITY, NY 11530			1752			
			DATE MAILED: 01/11/2006			

Please find below and/or attached an Office communication concerning this application or proceeding.

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Office Action Summary		Application	No.	Applicant(s)	E			
		10/679,782		ANGELOPOULOS ET AL.				
		Examiner		Art Unit				
		Sin J. Lee		1752				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply								
WHIC - External after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DANSIONS of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. Operiod for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS 36(a). In no event, will apply and will ex , cause the applica	COMMUNICATION however, may a reply be tim xpire SIX (6) MONTHS from tion to become ABANDONE	l. ely filed the mailing date of this co) (35 U.S.C. § 133).				
Status								
1)⊠	Responsive to communication(s) filed on 31 O	ctober 2005.						
2a) <u></u> □	<u> </u>							
3)□	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is							
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.								
Dispositi	ion of Claims							
5)□ 6)⊠ 7)□	Claim(s) <u>2-31</u> is/are pending in the application. 4a) Of the above claim(s) <u>14-29</u> is/are withdraw Claim(s) is/are allowed. Claim(s) <u>2-13,30 and 31</u> is/are rejected. Claim(s) is/are objected to. Claim(s) <u>2-31</u> are subject to restriction and/or expressions.	vn from consi						
Applicati	on Papers			-				
10)⊠	The specification is objected to by the Examine The drawing(s) filed on <u>06 October 2003</u> is/are: Applicant may not request that any objection to the Replacement drawing sheet(s) including the correction to one of the oath or declaration is objected to by the Ex	: a)⊠ accept drawing(s) be t ion is required	neld in abeyance. See if the drawing(s) is obj	37 CFR 1.85(a). ected to. See 37 CF	R 1.121(d).			
	ınder 35 U.S.C. § 119							
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 								
Attachmen 1) ⊠ Notic	t(s) e of References Cited (PTO-892)	4)	☐ Interview Summary	PTO-413)				
2) 🔲 Notic 3) 🔲 Inform	e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date	5)	Paper No(s)/Mail Da Notice of Informal Pa Other:	te	-152)			

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DETAILED ACTION

1. In view of the amendment of October 31, 2005, previous 102(b) rejection on claims 1, 2, 6, 7 and 11-13 over Mori et al. (JP'512) is hereby withdrawn.

2. Due to newly cited prior arts, the following rejection is made non-final.

Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims 2-13, 30 and 31 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hatakeyama et al (JP 2002-107938 and its machine-assisted English translation provided by JPO) in view of Angelopoulos et al (US 6,420,088 B1) and Pavelcheck et al (US 6,767,689 B2).

In Table 1 (see [0048] and abstract), Hatakeyama teaches an antireflective coating composition No.6 containing a polymer 1, a crosslinking agent CR2, an acid generator AG 1. Hatakeyama's Polymer 1 is shown below (see [0043]):

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Hatakeyama's CR2 is shown below (see [0045]):

, and this compound teaches present glycoluril crosslinking component.

Hatakeyama's AG 1 is shown below (see [0045]):

(AG1)

Hatakeyama's Polymer 1 shown above contains present Si-(Si)n moieties of Formula III and present reactive site of alcohol (–CH₂-CH₂-OH).

Hatakeyama does not teach present chromophore moieties in its polymer.

Angelopoulos et al teaches (col.1, lines 63-67, col.2, lines 1-3) a polymer (used in antireflective composition) having *pendant chromophore* moieties. Angelopoulos teaches that such polymer provides an antireflective composition having outstanding optical, mechanical and dry etch selectivity properties. As a preferred chromophore group, Angelopoulos teaches 9-anthracenemethyl group (see Example 1 and col.4, line 17). Besides, as evidenced by Pavelcheck et al, it is also known in the art to use a resin having pendant chromophore groups in an antireflective composition in order to absorb undesired radiation used to expose an overacted resist layer from reflecting back into

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the resist layer (see col.2, lines 41-61). Based on the teachings of Angelopoulos and Pavelcheck, it would have been obvious to one skilled in the art to incorporate a chromophore moiety (such as 9-anthracene<u>methyl</u> group) as a pendant group into Hatakeyama's polymer in order to obtain an antireflective composition having outstanding optical, mechanical and dry etch selectivity properties and also to absorb undesired radiation used to expose the overacted resist layer from reflecting back into the resist layer. Therefore, Hatakeyama in view of Angelopoulos and Pavelcheck would render obvious present silicon polymer of claims 3, 30 and 31 and thus render obvious present inventions of claims 2-13, 30 and 31.

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Sin J. Lee whose telephone number is 571-272-1333. The examiner can normally be reached on Monday-Friday from 9:00 am EST to 5:30 pm EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly, can be reached on 571-272-1526. The fax phone number for the organization where this application or proceeding is assigned is **571-273-8300**.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR.

Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

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you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

S. Lee

January 7, 2006

SIN LEE

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